

Electronic Supplementary Information

## **Formation of Internal P–N Junctions in Ta<sub>3</sub>N<sub>5</sub> Photoanodes for Water Splitting**

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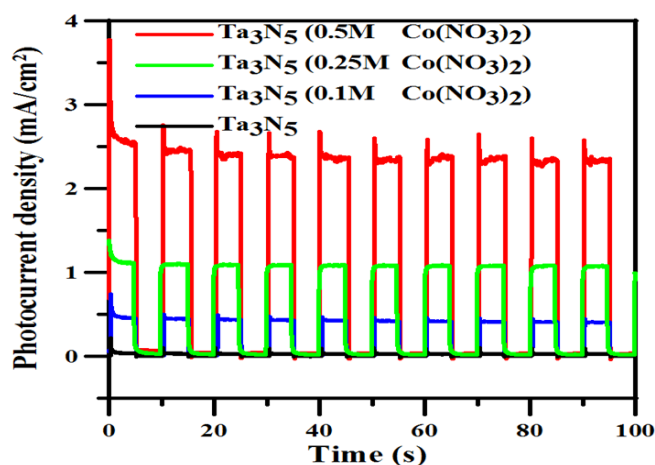
(Fax): 886-6-2344496

### **Electronic Supplementary Information for:**

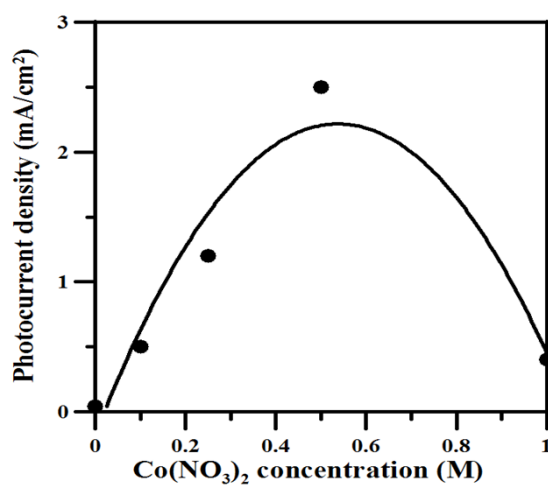
- 1. The influence of the Co-doping degree on the photoelectrochemical performance of the Ta<sub>3</sub>N<sub>5</sub>-based photoanodes.**
- 2. The Co 2p<sub>3/2</sub> XPS spectra of the Ta<sub>3</sub>N<sub>5</sub>:Co film.**
- 3. The photocurrents exhibited by the bare Ta and the Ta<sub>3</sub>N<sub>5</sub>:Co electrodes in a polysulfide redox couple (S<sup>2-</sup>/S<sub>x</sub><sup>2-</sup>) solution.**
- 4. Calculation of solar energy conversion efficiency of the Ta<sub>3</sub>N<sub>5</sub>:Co photoanode.**
- 5. A stability test of the Ta<sub>3</sub>N<sub>5</sub>:Co electrode by conducting a long-time photoelectrochemical reaction.**

# 1. The influence of the Co-doping degree on the photoelectrochemical performance of the $\text{Ta}_3\text{N}_5$ -based photoanodes

(a)

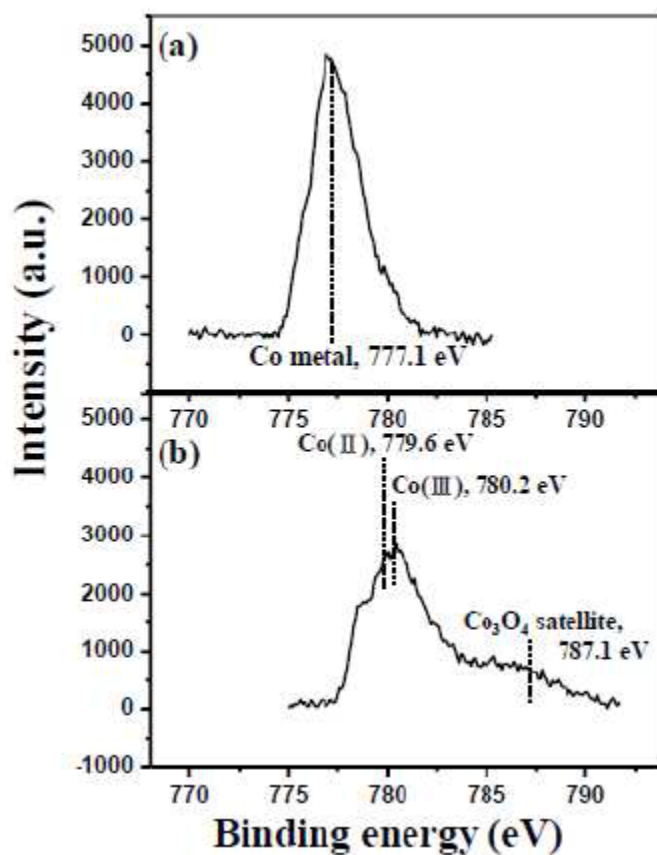


(b)



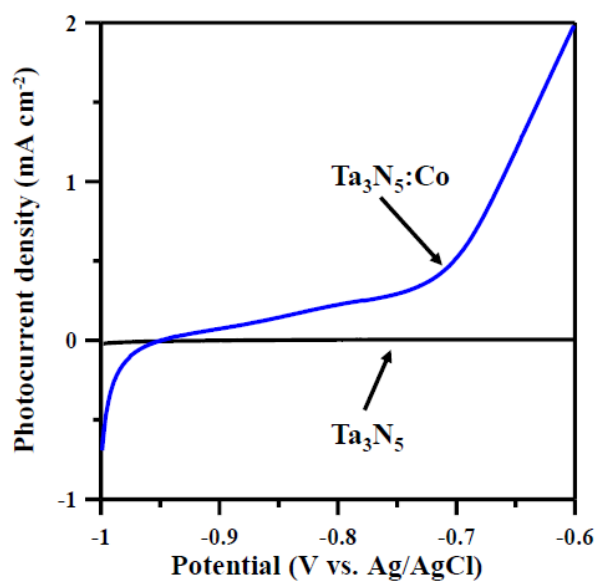
**Figure S1.** (a) Photoresponse of the  $\text{Ta}_3\text{N}_5$ :Co photoanodes obtained at an anodic bias of 0.5 V vs. Ag/AgCl and illuminated with chopped AM 1.5G simulated sunlight at  $100 \text{ mW cm}^{-2}$ . The photoanodes were obtained using  $\text{Co}(\text{NO}_3)_2$  soaking solutions of varying concentrations (0–1 M). The electrolyte is a 0.5-M KOH aqueous solution (pH=13.6). (b) Variation of the photocurrent with the concentration of the  $\text{Co}(\text{NO}_3)_2$  soaking solution.

## 2. The Co 2p<sub>3/2</sub> XPS spectra of the Ta<sub>3</sub>N<sub>5</sub>:Co film



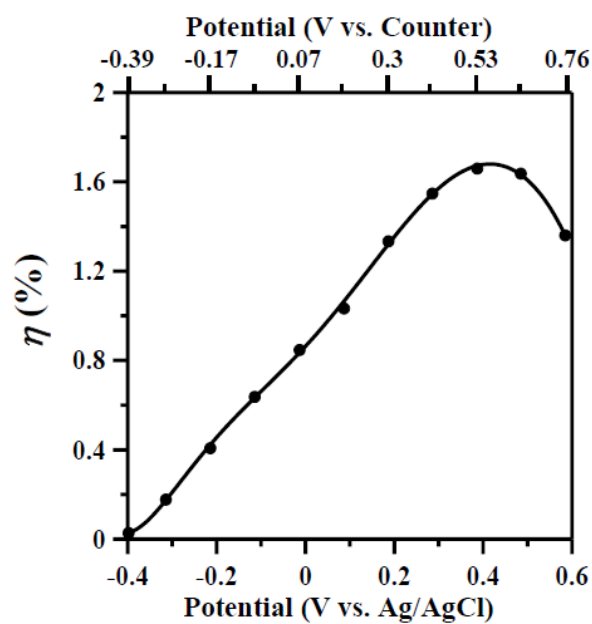
**Figure S2.** (a) The Co 2p<sub>3/2</sub> XPS spectra of the as-received Ta<sub>3</sub>N<sub>5</sub>:Co film. The Co ions likely belong to Co<sub>5.47</sub>N because their binding energy is close to that of Co metal. (b) The Co 2p<sub>3/2</sub> XPS spectra of the Ta<sub>3</sub>N<sub>5</sub>:Co film after the PEC reaction. The Co ions were oxidized to high-valence Co ions, likely belonging to Co<sub>2</sub>O<sub>3</sub>/Co<sub>3</sub>O<sub>4</sub> (i.e., CoO<sub>x</sub>).<sup>1,2</sup>

**3. The photocurrents exhibited by the bare Ta and the Ta<sub>3</sub>N<sub>5</sub>:Co electrodes in a polysulfide redox couple (S<sup>2-</sup>/S<sub>x</sub><sup>2-</sup>) solution**



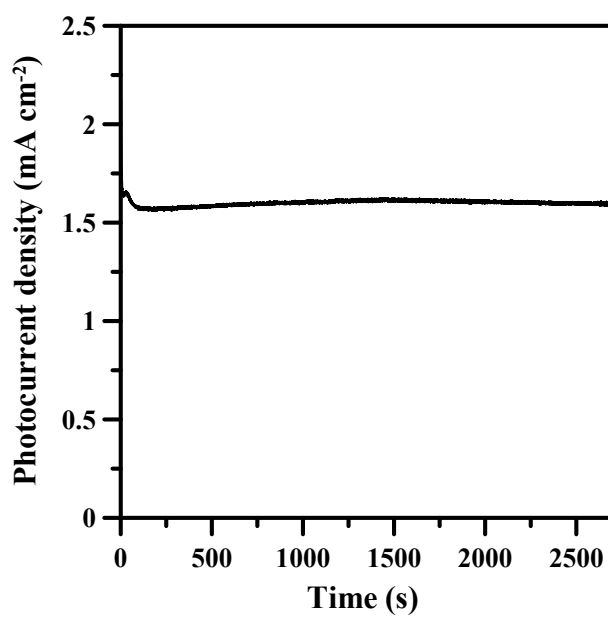
**Figure S3.** Current-potential characteristics of the Ta<sub>3</sub>N<sub>5</sub> and Ta<sub>3</sub>N<sub>5</sub>:Co photoanodes with an anodic scan applied at 10 mV s<sup>-1</sup> and illuminated with AM 1.5G simulated sunlight at 100 mW cm<sup>-2</sup>. The electrolyte is a fast polysulfide redox couple (S<sup>2-</sup>/S<sub>x</sub><sup>2-</sup>) aqueous solution containing 0.24 M Na<sub>2</sub>S and 0.35 M Na<sub>2</sub>SO<sub>3</sub>.

#### 4. Calculation of solar energy conversion efficiency of the Ta<sub>3</sub>N<sub>5</sub>:Co photoanode



**Figure S4.** Applied bias photon-to-current conversion efficiency ( $\eta$ ) of the Ta<sub>3</sub>N<sub>5</sub>:Co photoanode under varying bias potentials. The  $\eta$  values were calculated using the data of Fig. 7.<sup>3,4</sup>

**5. A stability test of the Ta<sub>3</sub>N<sub>5</sub>:Co electrode by conducting a long-time photoelectrochemical reaction**



**Figure S5.** Photoresponse of the Ta<sub>3</sub>N<sub>5</sub>:Co photoanode obtained at an anodic bias of 0.53 V vs. counter (or 0.39 V vs. Ag/AgCl) and illuminated with AM 1.5G simulated sunlight at 100 mW cm<sup>-2</sup>.

## References

1. L. An, W. Huang, N. Zhang, X. Chen and D. Xia, *J. Mater. Chem. A*, 2014, **2**, 62-65.
2. B. J. Tan, K. J. Klabunde, and P. M. A. Sherwood, *J. Am. Chem. Soc.* 1991, **113**, 855-861.
3. A. J. Nozik and J. Miller, *Chem. Rev.* 2010, **110**, 6443–6445.
4. Z. Chen, T. F. Jaramillo, T. G. Deutsch, A. Kleiman-Shwarscstein, A. J. Forman, N. Gaillard, R. Garland, K. Takanabe, C. Heske, M. Sunkara, E. W. McFarland, K. Domen, E. L. Miller, J. A. Turner and H. N. Dinh, *J. Mater. Res.* 2010, **25**, 3-16.